PHOTORESIST
MANUFACTURING & INNOVATION

KemLab Photoresist Product Selector

	Competitive Product(s)	Film Thickness µm																			Exp λ			Dev		
																					i-line	g-line	Broad-band	TMAH 0.26N	KOH / MIB	HARE SQ
NEGATIVE PHOTORESISTS																										
		0.2	0.5	0.75	1	1.5	2	2.5	3	4	5	6	7	8	9	10	20	30	40	50	100						
HARE SQ™ Premium High Aspect Ratio Negative Tone Epoxy																										
HARE SQ 2	*SU-8 2*																				x		x			x
HARE SQ 5	*SU-8 5*																				x		x			x
HARE SQ 10	*SU-8 10*																				x		x			x
HARE SQ 25	*SU-8 25*																				x		x			x
HARE SQ 50	*SU-8 50*																				x		x			x
APOL-LO Premium Negative Lift-Off																										
APOL-LO 3202	*AZ nLOF 2020*																				x		x	x	x	
APOL-LO 3204	*AZ nLOF 2035*																				x		x	x	x	
APOL-LO 3207	*AZ nLOF 2070*																				x		x	x	x	
NPR Negative with Vertical Profile																										
NPR 1																					x		x	x	x	
NPR 2	*AZ 15nXT Series*																				x		x	x	x	
NPR 4																					x		x	x	x	
NPR 6																					x		x	x	x	
NPR 10	*AZ 15nXT 450cP*																				x		x	x	x	
POSITIVE PHOTORESISTS																										
		0.2	0.5	0.75	1	1.5	2	2.5	3	4	5	6	7	8	9	10	20	30	40	50	100						
KL5300 General Purpose Positive Thin																										
KL 5302 Hi-Res																					x	x	x	x		
KL 5305	*S1805*																				x	x	x	x		
KL 5310	*S1811 / S1808*																				x	x	x	x		
KL 5315	*S1813 / S1818*																				x	x	x	x		
KL6000 General Purpose Positive Thick - MIF Developers																										
KL 6002	*S1818 / S1821*																				x	x	x	x		
KL 6003	*SPR220-3.0 /*																				x	x	x	x		
KL 6005	*SPR220-4.5*																				x	x	x	x		
KL 6008	*SPR220-7.0*																				x	x	x	x		
K-PRO™ Premium Advanced Packaging Positive Resist - Suitable for MIB Developers																										
K-PRO 1																					x	x	x	x	x	
K-PRO 2	*AZ 4000*																				x	x	x	x	x	
K-PRO 3																					x	x	x	x	x	
K-PRO 5																					x	x	x	x	x	
K-PRO 7																					x	x	x	x	x	
K-PRO 15	*AZ4620*																				x	x	x	x	x	
IMAGE REVERSAL PHOTORESIST																										
		0.2	0.5	0.75	1	1.5	2	2.5	3	4	5	6	7	8	9	10	20	30	40	50	100						
KL Image Reversal Image Reversal Standard and Lift-Off																										
KL IR-15 Lift-Off	*AZ5214 E IR*																				x	x	x	x		
KL IR-15																					x	x	x	x		
PMMA / CO-POLYMER E-BEAM PHOTORESISTS																										
		0.05	0.07	0.1	0.15	0.2	0.3	0.4	0.5	0.6	0.7	0.8	1.1	2.0	2.5	3.0	4.0									
HARP™ PMMA and Copolymer High Aspect Ratio Positive e-Beam																										
500 HARP	*495 PMMA A*																									
1000 HARP	*950 PMMA A*																									
HARP-C	*MMA(8.5)MAA*																									